

## The Aggregates in LB Films of Schiff base Aluminium (III) Complex

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**Abstract:** The surface pressure-area ( $\pi$ -A) isotherm of Schiff base aluminium (III), tris (2-hydroxy-5-nitro-N-dodecyl-benzylideneaminato) aluminium (III) (denoted as Al(TA12)<sub>3</sub>), on pure water subphase was investigated. The molecular area, 0.48 nm<sup>2</sup>, is one-third of expected value that indicated the aggregation took place. The Langmuir-Blodgett (LB) films of Al(TA12)<sub>3</sub> was transferred and characterized. The AFM image confirmed the formation of aggregates.

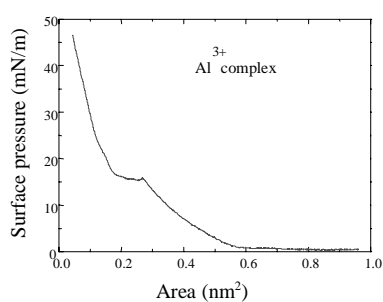
**Keywords:** Aluminium (III)-Schiff base complex, LB films, aggregate, AFM image.

Metal complexes, which are composed of metal ions and amphiphile ligands, show some structural peculiarities in Langmuir-Blodgett (LB) films. In the past studies, the metal complexes were mainly composed of the transitional metal ions<sup>1,2</sup>. The metal ions in IA, IIA and IIIA were seldom mentioned. Further more, the aluminium element is at the position where the typical metal elements transit to the typical non-metal elements in the periodic table of elements and study on the properties of Al<sup>3+</sup> complexes LB films is not so much<sup>3</sup>. In this work, we investigated the monolayer behavior and LB films characteristics of this complex.

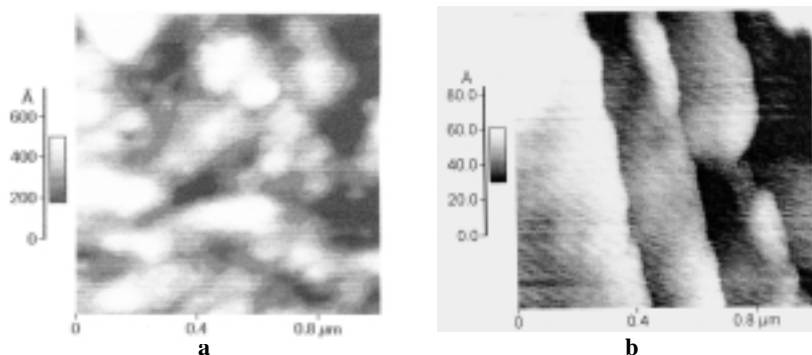
**Figure 1** is the surface pressure-area isotherm of Al(TA12)<sub>3</sub>. It illustrates that the metal complex can form stable Langmuir film on the water surface. But in lower pressure region below 15 mN/m, the collapse area, 0.48 nm<sup>2</sup>, is much smaller than we expect. It is known that the headgroup consisting of the phenyl ring and the chelating ring is about 0.5nm<sup>2</sup> and the collapse area of a similar metal complex Cu(SA16)<sub>2</sub> is 0.9 nm<sup>2,4</sup>. There are three headgroups in Al(TA12)<sub>3</sub> and its area should be about 1.5 nm<sup>2</sup>. The collapse area should have nothing with the length of the hydrophobic chains. One reason may be that the radii of Al<sup>3+</sup> (0.5Å) is much smaller than that of Cu<sup>2+</sup> (0.72Å) and the other is that the plane of each headgroup can not oriented in a same plane parallel to the water surface and the planes should aggregate. If the headgroups are in the same plane, it will be more crowded and the chelating atoms can not be form stable bond with Al<sup>3+</sup>. So the plane of each headgroup is supposed to be oriented with an angle to the subphase surface. In the region of surface pressure from 15 mN/m to 18 mN/m, the non-horizontal plateau indicates a collapse process. And in the higher surface pressure region, an area of 0.2 nm<sup>2</sup> was observed that indicates non-order aggregates.

The AFM images of LB films of Al(TA12)<sub>3</sub> are displayed in **Figure 2**. In **Figure 2a**, the LB film was transferred in 20 mN/m and the image shows many non-order aggregates. While in **Figure 2b**, when the LB film was transferred in 10 mN/m, a piece aggregate structure was observed. In that the size of parallel with the barrier is very long and of vertical with the barrier is about 0.2 μm.

**Figure 1** Surface pressure-area isotherm of Al(TA12)<sub>3</sub> on pure water



**Figure 2** The AFM image of the metal complex



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